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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/029,093	12/21/2001	Mariam G. Sadaka	SC11464ZP	3417
23330 7	7590 10/03/2003	EXAMINER		NER
MOTOROLA, INC. CORPORATE LAW DEPARTMENT - #56-238 3102 NORTH 56TH STREET PHOENIX, AZ 85018			PHAM, LONG	
			ART UNIT	PAPER NUMBER
			2814	
		DATE MAILED: 10/03/2003		

Please find below and/or attached an Office communication concerning this application or proceeding.

		Application No.	Applicant(s)				
		10/029,093	SADAKA ET AL.				
	Office Action Summary	Examiner	Art Unit				
		Long Pham	2814				
The MAILING DATE of this communication appears on the cover sheet with the correspondence address Period for Reply							
A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) FROM THE MAILING DATE OF THIS COMMUNICATION. - Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication. - If the period for reply specified above is less than thirty (30) days, a reply within the statutory minimum of thirty (30) days will be considered timely. - If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication. - Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133). - Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b). Status							
1)	Responsive to communication(s) filed on						
2a)		– s action is non-final.					
3)	·						
Disposition of Claims							
4)⊠ Claim(s) <u>1-35</u> is/are pending in the application.							
4a) Of the above claim(s) is/are withdrawn from consideration.							
5)	Claim(s) is/are allowed.						
6)⊠ Claim(s) <u>1-35</u> is/are rejected.							
7)	7) Claim(s) is/are objected to.						
8) Claim(s) are subject to restriction and/or election requirement.							
· · ·	on Papers						
9) The specification is objected to by the Examiner.							
10) The drawing(s) filed on is/are: a) accepted or b) objected to by the Examiner.							
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).							
11) The proposed drawing correction filed on is: a) approved b) disapproved by the Examiner.							
If approved, corrected drawings are required in reply to this Office action.							
12) The oath or declaration is objected to by the Examiner.							
Priority under 35 U.S.C. §§ 119 and 120							
13) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f). a) All b) Some * c) None of:							
 1. Certified copies of the priority documents have been received. 2. Certified copies of the priority documents have been received in Application No 							
Copies of the certified copies of the priority documents have been received in this National Stage							
application from the International Bureau (PCT Rule 17.2(a)). * See the attached detailed Office action for a list of the certified copies not received.							
14) Acknowledgment is made of a claim for domestic priority under 35 U.S.C. § 119(e) (to a provisional application).							
a) ☐ The translation of the foreign language provisional application has been received. 15)☐ Acknowledgment is made of a claim for domestic priority under 35 U.S.C. §§ 120 and/or 121.							
Attachment(s)							
2) Notice	e of References Cited (PTO-892) e of Draftsperson's Patent Drawing Review (PTO-948) nation Disclosure Statement(s) (PTO-1449) Paper No(s)	5) 🔲 Notice of Informal I	y (PTO-413) Paper No(s) Patent Application (PTO-152)				

Application/Control Number: 10/029,093 Page 2

Art Unit: 2814

DETAILED ACTION

Claim Rejections - 35 USC § 112

- 1. The following is a quotation of the second paragraph of 35 U.S.C. 112:

 The specification shall conclude with one or more claims particularly pointing out and distinctly claiming the subject matter which the applicant regards as his invention.
- 2. Claims 1-18 and 19-23 are rejected under 35 U.S.C. 112, second paragraph, as being indefinite for failing to particularly point out and distinctly claim the subject matter which applicant regards as the invention.

In claim 1, line 5, it is unclear what "first liquid composition" encompasses. In claim 19, line 6, it is unclear what "first etchant" encompasses.

3. Claim 5 is objected to under 37 CFR 1.75(c), as being of improper dependent form for failing to further limit the subject matter of a previous claim. Applicant is required to cancel the claim(s), or amend the claim(s) to place the claim(s) in proper dependent form, or rewrite the claim(s) in independent form. " the second composition is a dilute aqueous solution" does not further limit the limitation of "the second composition ... comprising HCl and H₂O₂".

Claim Rejections - 35 USC § 102

4. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

- (b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.
- 5. Claim 24 is rejected under 35 U.S.C. 102(b) as being anticipated by Chino (US '894).

Application/Control Number: 10/029,093 Page 3

Art Unit: 2814

Chino teaches a method for etching a substrate, comprising steps of: providing a substrate 1 comprising formations InP; etching the formations with a composition comprising a dilute aqueous solution of H₂O₂ and HCI. See [0049] to [0050].

Claim Rejections - 35 USC § 103

- 6. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 7. Claims 25-28 rejected under 35 U.S.C. 103(a) as being unpatentable over Chino (US '894).

With claims 25-27, Chino fails to teach the ranges for the mole ratio of H₂O₂ to HCl.

However, it would have been obvious to one of <u>ordinary skill</u> in the art of making semiconductor devices to determine the workable or optimal ranges for the mole ratio of H₂O₂ to HCl through routine experimentation and optimization to obtain optimal or desired device performance because the mole ratio of H₂O₂ to HCl is a result-effective variable and there is no evidence indicating that it is critical or produces any unexpected results and it has been held that it is not inventive to discover the optimum or workable ranges of a result-effective variable within given prior art conditions by routine experimentation. See MPEP 2144.05.

8. Claims 29-33 are rejected under 35 U.S.C. 103(a) as being unpatentable over Derwent 2001-317714 (Hayakawa (US '297)).

Application/Control Number: 10/029,093 Page 4

Art Unit: 2814

With respect to claims 29-33, Derwent '714 teaches a method comprising the steps of:

providing a substrate comprising a plurality of epitaxial layers containing a first layer of GaAs and a second layer of InGaAs;

etching the interface with a composition comprises H2O2, HCI, and H2O. See col. 7, lines 45-60.

Derwent '714 fails to teach that the second layer or active layer is made of InGaP.

However, the use of InGaP as active layer in forming a field effect transistor or light emitting device is well-known.

9. Claims 34-35 are rejected under 35 U.S.C. 103(a) as being unpatentable over Derwent 2001-317714 (Hayakawa (US '297)).

With respect to claims 34-35, Derwent '714 fails to teach the ranges for the concentration of HCI in the liquid medium.

However, it would have been obvious to one of <u>ordinary skill</u> in the art of making semiconductor devices to determine the workable or optimal ranges for the concentration of HCl in the liquid medium through routine experimentation and optimization to obtain optimal or desired device performance because the concentration of HCl in the liquid medium is a result-effective variable and there is no evidence indicating that it is critical or produces any unexpected results and it has been held that it is not inventive to discover the optimum or workable ranges of a result-effective variable within given prior art conditions by routine experimentation. See MPEP 2144.05.

Application/Control Number: 10/029,093

Art Unit: 2814

Allowable Subject Matter

10. Claims 1-18 and 19-23 are objected to as being dependent upon a rejected base claim, but would be allowable if rewritten in independent form including all of the limitations of the base claim and any intervening claims.

Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Long Pham whose telephone number is 703-308-1092. The examiner can normally be reached on M-F, 8:30AM-5:00PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Wael Fahmy can be reached on 703-308-4918. The fax phone numbers for the organization where this application or proceeding is assigned are 703-746-4082 for regular communications and 703-746-4082 for After Final communications.

Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the receptionist whose telephone number is 703-308-0956.

Long Pham

Primary Examiner

Page 5

Art Unit 2814

L. P.

September 19, 2003